

ABSTRACT OF THE DISCLOSURE

The invention concerns a photolithography fabrication method enabling production of patterns in a photosensitive resin layer (601) placed on a substrate (600). The patterns (607) comprise flanks (608) 5 inclined relative to a normal ( $\vec{n}$ ) relative to the principal plane of the substrate and which have an angle of inclination ( $\theta$ ) far greater to that of the patterns obtained according to the prior art.

The invention also concerns a device allowing said 10 method to be executed.

Figure 13A.